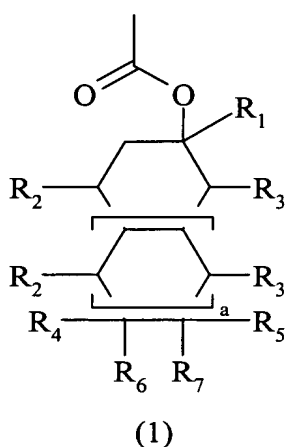


1. **(Currently Amended)** A polymer containing a group of the following general formula (1) and having a weight average molecular weight of 1,000 to 500,000,

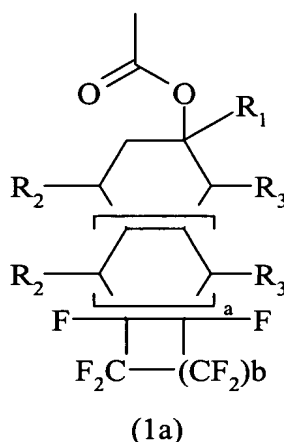


R<sup>6</sup> and R<sup>7</sup> each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, at least one of R<sup>6</sup> and R<sup>7</sup> contains at least one fluorine atom, or alternatively R<sup>6</sup> and R<sup>7</sup> may bond together to form a ring and in that event,

each is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms, and

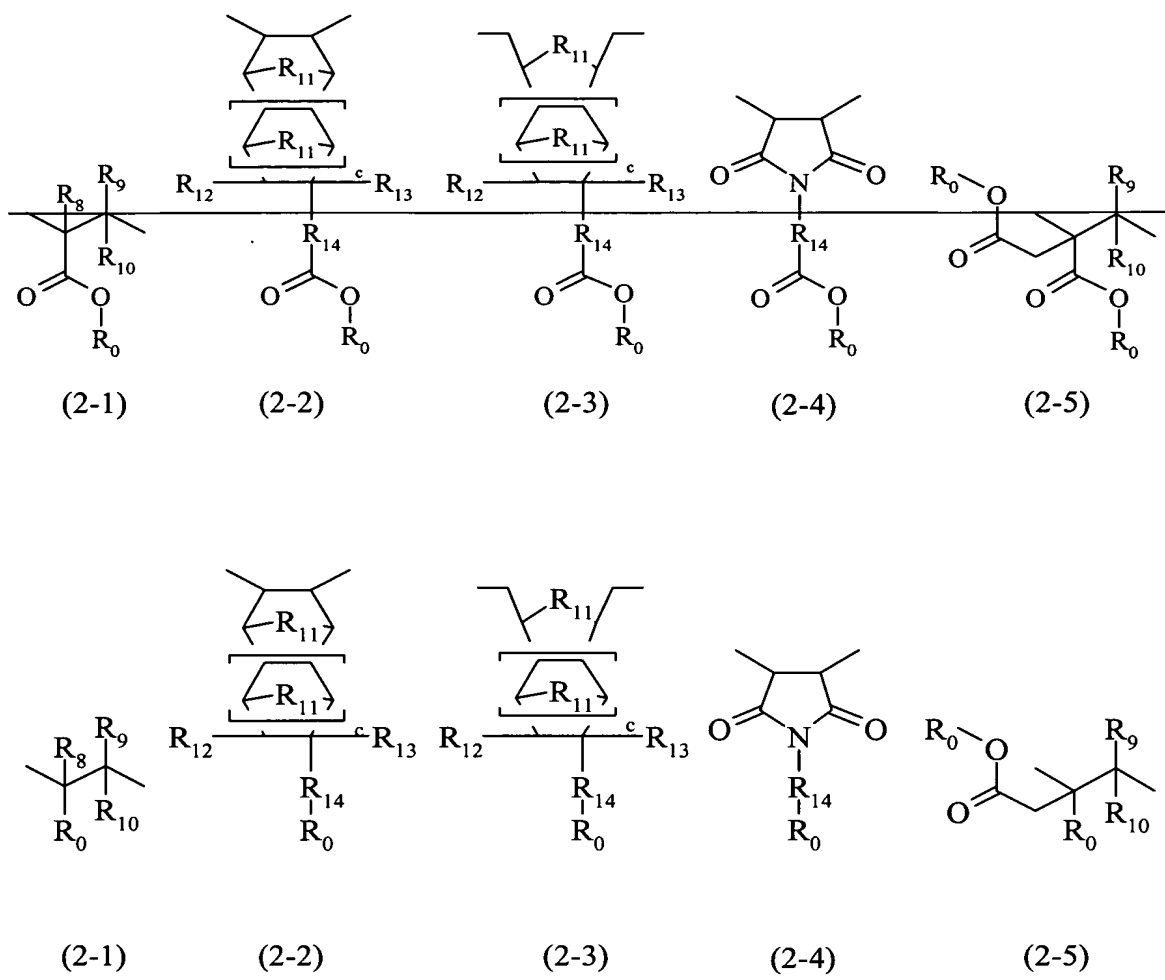
"a" is 0 or 1.

2. (Currently Amended) The A polymer of ~~claim 1~~ containing a group of the following ~~general~~ formula (1a) and having a weight average molecular weight of 1,000 to 500,000:



wherein  $R^1$  to  $R^3$  each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms, or alternatively  $R^2$  and  $R^3$  ~~may~~ bond together to form a ring and in that event, each is an alkylene group of 1 to 20 carbon atoms which ~~may~~ contain optionally contains a hetero atom such as oxygen, sulfur or nitrogen, "a" is 0 or 1, and "b" is an integer of 1 to 4.

3. (Currently Amended) The polymer of claim 1 having a partial structure of any one of the following ~~general~~ formulae (2-1) to (2-5):



wherein  $R^0$  is a group of formula (1) in claim 1 or a group of formula (1a) in claim 2,

$R^8$  to  $R^{10}$  each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms,

$R^{11}$  is a methylene group, oxygen atom or sulfur atom,

$R^{12}$  and  $R^{13}$  each are hydrogen, methyl or  $\text{CH}_2\text{CO}_2\text{R}^{15}$ ,

$R^{14}$  is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms,

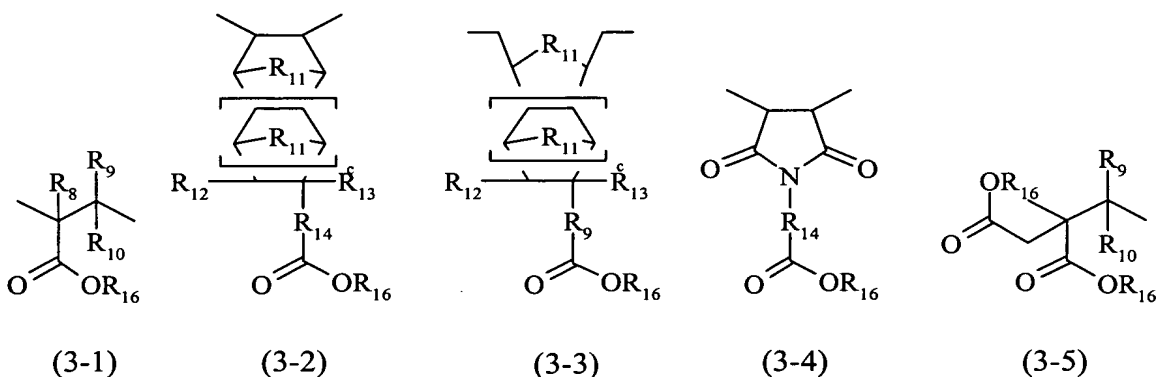
R<sup>15</sup> is a straight, branched or cyclic alkyl or substituted alkyl group of 1 to 20 carbon atoms, and

“c” is 0 or 1.

4.     **(Original)**     A resist composition comprising the polymer of claim 1.
  
5.     **(Previously presented)**     A chemically amplified, positive resist composition comprising
  - (A) the polymer of claim 1,
  - (B) an organic solvent, and
  - (C) a photoacid generator.
  
6.     **(Original)**     The resist composition of claim 5 further comprising (D) a basic compound.
  
7.     **(Original)**     The resist composition of claim 5 further comprising (E) a dissolution inhibitor.
  
8.     **(Original)**     A process for forming a resist pattern comprising the steps of:
  - applying the resist composition of claim 4 onto a substrate to form a coating,
  - heat treating the coating and then exposing it to high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photo mask, and
  - optionally heat treating the exposed coating and developing it with a developer.

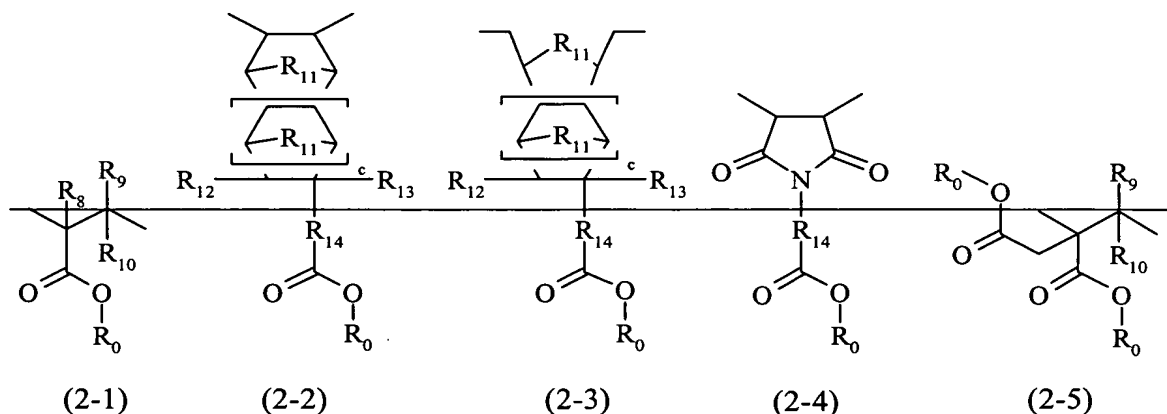
9. (Original) The pattern forming process of claim 8 wherein the high-energy radiation is an F<sub>2</sub> laser beam, Ar<sub>2</sub> laser beam or soft x-ray.

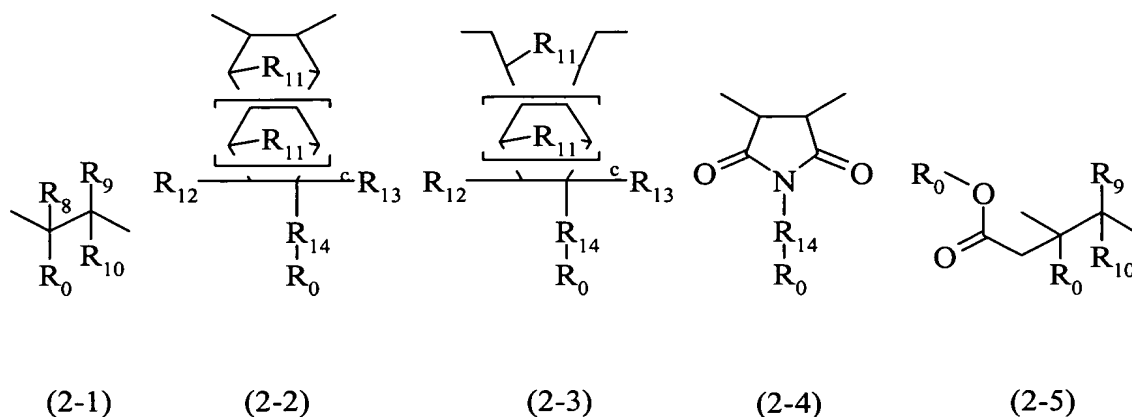
10. (New) The polymer of claim 3 which additionally comprises recurring units of one of formulae (3-1) to (3-5):



wherein, R<sup>8</sup> to R<sup>15</sup> and c are as defined above, and R<sup>16</sup> is an acid labile group.

11. (New) The polymer of claim 2 having a partial structure of any one of the following formulae (2-1) to (2-5):





wherein R<sup>0</sup> is a group of formula (1a) in claim 2,

R<sup>8</sup> to R<sup>10</sup> each are hydrogen, fluorine or a straight, branched or cyclic alkyl or fluorinated alkyl group of 1 to 20 carbon atoms,

R<sup>11</sup> is a methylene group, oxygen atom or sulfur atom,

R<sup>12</sup> and R<sup>13</sup> each are hydrogen, methyl or CH<sub>2</sub>CO<sub>2</sub>R<sup>15</sup>,

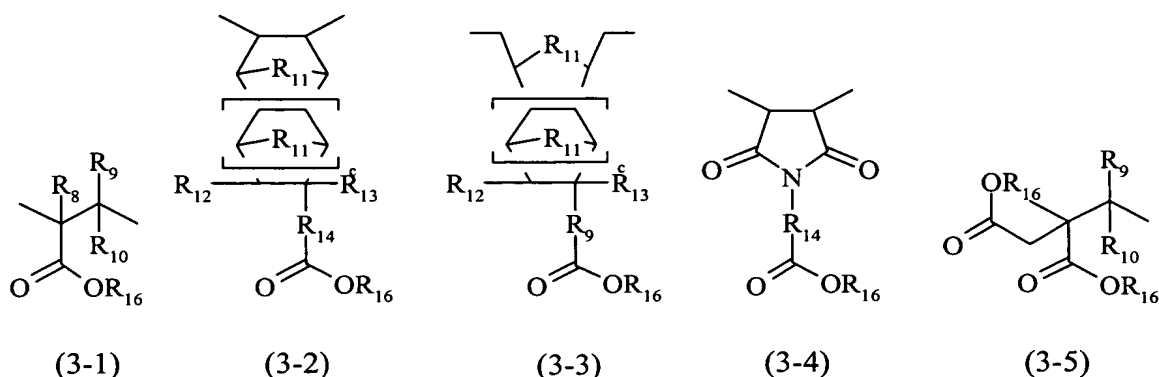
R<sup>14</sup> is a straight, branched or cyclic alkylene or fluorinated alkylene group of 1 to 20 carbon atoms,

R<sup>15</sup> is a straight, branched or cyclic alkyl or substituted alkyl group of 1 to 20 carbon atoms, and

“c” is 0 or 1.

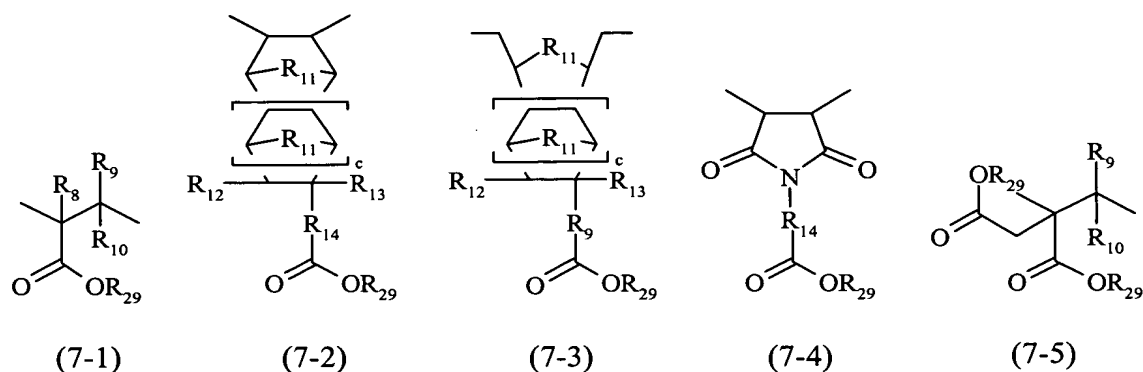
12. (New) A resist composition comprising the polymer of claim 2.

13. (New) A chemically amplified, positive resist composition comprising
  - (A) the polymer of claim 2,
  - (B) an organic solvent, and
  - (C) a photoacid generator.
14. (New) The resist composition of claim 13 further comprising (D) a basic compound.
15. (New) The resist composition of claim 13 further comprising (E) a dissolution inhibitor.
16. (New) A process for forming a resist pattern comprising the steps of:
  - applying the resist composition of claim 12 onto a substrate to form a coating,
  - heat treating the coating and then exposing it to high-energy radiation in a wavelength band of 100 to 180 nm or 1 to 30 nm through a photo mask, and
  - optionally heat treating the exposed coating and developing it with a developer.
17. (New) The pattern forming process of claim 16 wherein the high-energy radiation is an F<sub>2</sub> laser beam, Ar<sub>2</sub> laser beam or soft x-ray.
18. (New) The polymer of claim 11 which additionally comprises one or more recurring units of one of formulae (3-1) to (3-5):



wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{16}$  is an acid labile group.

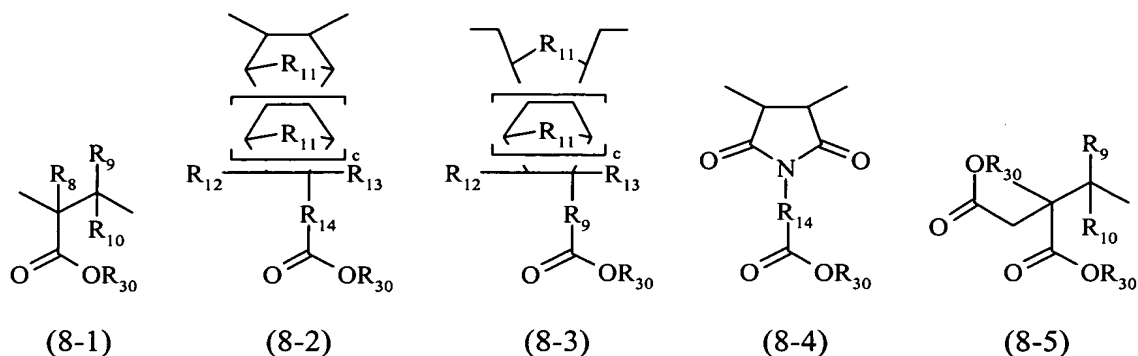
19. (New) The polymer of claim 3 which additional comprises one or more recurring units of one of the formulae (7-1) to (7-5)



wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{29}$  is a fluorinated alkyl group having 2 to 20 carbon atoms.

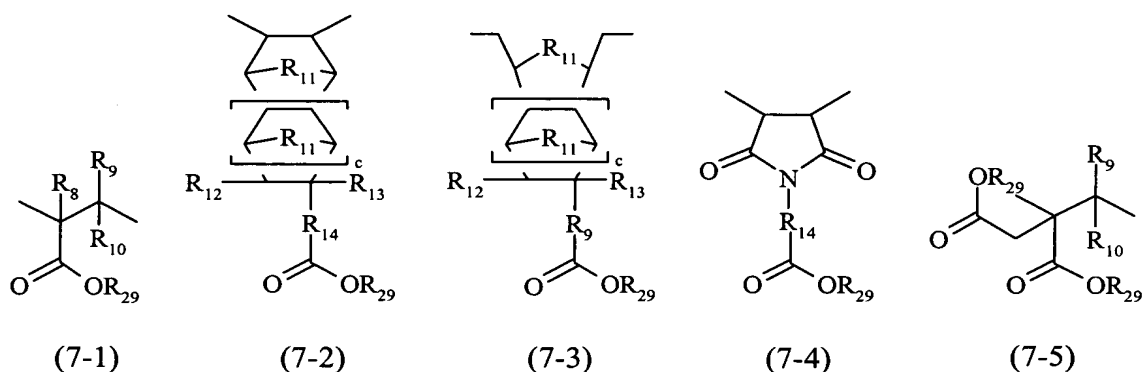
20. (New) The polymer of claim 3 which additional comprises one or more recurring units of one of the formulae (8-1) to (8-5):





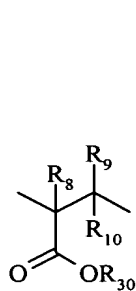
wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{30}$  is hydrogen or an adhesive group.

21. (New) The polymer of claim 11 which additional comprises one or more recurring units of one of the formulae (7-1) to (7-5)

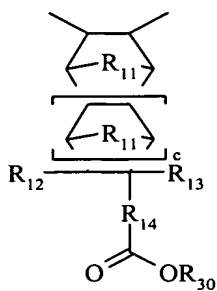


wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{29}$  is a fluorinated alkyl group having 2 to 20 carbon atoms.

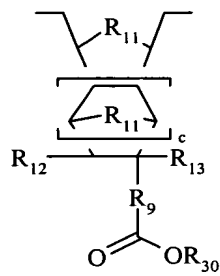
22. (New) The polymer of claim 11 which additional comprises one or more recurring units of one of the formulae (8-1) to (8-5):



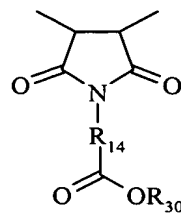
(8-1)



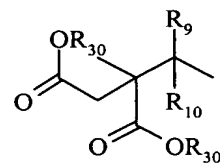
(8-2)



(8-3)



(8-4)



(8-5)

wherein,  $R^8$  to  $R^{15}$  and  $c$  are as defined above, and  $R^{30}$  is hydrogen or an adhesive group.